

This listing of the claims will replace all prior versions, and listings, of claims in the application:

**LISTING OF THE CLAIMS**

1-23. (canceled)

24. (currently amended) A substrate having a patterned surface, comprising:

(a) a substrate having a surface with first regions that correspond to a desired surface pattern and second regions that correspond to the inverse of the desired surface pattern;

(b) a first self-assembled monolayer of a first molecular moiety covalently bound to the surface within the first regions; and

(c) a polymeric overlayer comprised of a polymer bound to the first molecular moiety;

wherein a molecular moiety -A-B is bound to the surface within the second regions, wherein A is a linking group and B is an inert molecular segment.

25. (previously presented) The substrate of claim 24, further comprising: (d) a second self-assembled monolayer of a second molecular moiety bound to the surface in the second regions.

26. (original) The substrate of claim 24, wherein the substrate surface is metallic.

27. (original) The substrate of claim 24, wherein the substrate surface is comprised of a metal oxide.

28. (original) The substrate of claim 24, wherein the substrate surface is silicon-containing.

29. (original) The substrate of claim 24, wherein the substrate surface is polymeric.

30. (canceled)

31. (currently amended) The substrate of claim ~~30~~ 24, wherein the molecular moiety -A-B forms a second self-assembled monolayer.

32. (currently amended) The substrate of claim ~~30~~ 24, wherein B is hydrocarbyl of 1 to 20 carbon atoms containing 0 to 6 ether linkages.

33. (previously presented) The substrate of claim 31, wherein B is saturated alkyl containing 1 to 15 carbon atoms and 0 to 4 ether linkages.

34. (previously presented) The substrate of claim 31, wherein the molecular moiety -A-B is provided by reaction of the surface with a reactant having the structure A-B, in which A is selected from the group consisting of -OH, -SH, -NH<sub>2</sub>, -CONH<sub>2</sub>, -COOH, -SO<sub>3</sub>H, -CN, -PO<sub>3</sub>H, -SiCl<sub>3</sub>, -SiR<sub>2</sub>Cl, -SR and -SSR wherein R is alkyl or aryl.

35. (previously presented) The substrate of claim 32, wherein the molecular moiety -A-B is provided by reaction of the surface with a reactant having the structure A-B, in which A is selected from the group consisting of -OH, -SH, -NH<sub>2</sub>, -CONH<sub>2</sub>, -COOH, -SO<sub>3</sub>H, -CN, -PO<sub>3</sub>H, -SiCl<sub>3</sub>, -SiR<sub>2</sub>Cl, -SR and -SSR wherein R is alkyl or aryl.

36. (previously presented) The substrate of claim 24, wherein the first molecular moiety has the structure -A'-L-C wherein A' is a surface binding moiety, L is a linker, and C is a molecular segment terminating in a functional group that in turn binds to said polymer.

37. (previously presented) The substrate of claim 36, wherein:  
A' is selected from the group consisting of -OH, -SH, -NH<sub>2</sub>, -CONH<sub>2</sub>, -COOH, -SO<sub>3</sub>H, -CN, -PO<sub>3</sub>H, -SiCl<sub>3</sub>, -SiR<sub>2</sub>Cl, -SR and -SSR wherein R is alkyl or aryl;  
L is hydrocarbylene of 1 to 20 carbon atoms containing 0 to 6 ether linkages; and  
C is selected from the group consisting of -OH, -NH<sub>2</sub>, -COOH, -SO<sub>3</sub>H, -CN, alkoxyamine, azo, peroxide, halide and sulfonyl halide.

38. (previously presented) The substrate of claim 37, wherein L is saturated alkylene containing 1 to 15 carbon atoms and 0 to 4 ether linkages.

39. (previously presented) The substrate of claim 24, wherein the second regions have been treated with an etching reagent.

40. (previously presented) The substrate of claim 24, wherein the polymeric overlayer is comprised of a polymer prepared by polymerization of monomers selected from the group consisting of vinyl monomers and cyclic esters.